



PATENT  
Customer No. 23494  
Attorney Docket No. TI-25250  
Application No.: 09/199,829

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Application of:

SMITH et al.

Application No.: 09/199,829

Filed: November 25, 1998

For: HYDROGEN PLASMA  
PHOTORESIST STRIP AND  
POLYMERIC RESIDUE CLEANUP  
PROCESS FOR OXYGEN-  
SENSATIVE MATERIALS

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) Group Art Unit: 2823

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) Examiner: Julio J. MALDONADO  
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**MAIL STOP AMENDMENT**  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

**PETITION FOR EXTENSION OF TIME**

Applicant hereby petitions for a one month extension of time to reply to the Office Action of June 14, 2005.

Please grant any extensions of time required to enter this response and charge any additional required fees to the Texas Instruments Deposit Account 20-0668.

Respectfully submitted,

Dated: October 5, 2005

By: 

Jonathan A. Hack  
Reg. No. 47,623

Timothy M. Hsieh  
Reg. No. 42,672

10/06/2005 JADD01 00000145 200668 09199829

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